

Pfeiffer Vacuum+Fab Solutions to Showcase Advanced Semiconductor Technologies at SEMICON India 2026

Pfeiffer Vacuum+Fab Solutions, a member of the global Busch Group, will exhibit at SEMICON India 2026 from September 17 to 19 at Yashobhoomi, New Delhi, India.

ASSLAR, GERMANY, August 14, 2026 /EINPresswire.com/ -- As India continues to expand its semiconductor industry, Pfeiffer will present advanced contamination management and gas abatement technologies that enhance efficiency across the entire chip manufacturing process. At the trade show booth, visitors can explore solutions designed to increase yield, strengthen process reliability, and contribute to more sustainable production. Visitors can meet the team in hall 1, booth 945.



A highlight of the Pfeiffer booth at SEMICON India will be a virtual tour through a modern semiconductor manufacturing facility. Source: Pfeiffer Vacuum+Fab Solutions.

Contamination Management Solutions for improved yield

Through several 3D models, visitors can explore the contamination management portfolio from Pfeiffer, designed for the demanding conditions of [semiconductor manufacturing](#). Drawing on decades of experience, the company offers a comprehensive range of technologies for measuring, controlling and cleaning airborne molecular contamination. The [Ambient Multi-Port Controller \(AMPC\)](#), for example, enables manufacturers to monitor and analyze contamination data, which can be transmitted to fab control software for better process control and optimization. The APA pod analyzer detects contamination to improve FOUP cleaning efficiency, maximize wafer yield, manage wafer Q-Time, pinpoint the sources of defects, and maintain contamination control throughout cleanroom operations.

Gas Abatement Systems for cleaner semiconductor manufacturing

A 3D model will present one system from the company's comprehensive gas abatement portfolio for semiconductor and other high-tech manufacturing applications. Installed directly at the process tool, these systems efficiently reduce hazardous process gases, including those with high global warming potential. Using proven thermal, wet, dry adsorption, and filtration technologies, the portfolio addresses demanding applications such as etching, chemical vapor deposition (CVD), atomic layer deposition (ALD), and EUV lithography. By helping manufacturers reduce emissions while maintaining safe and reliable operations, the solutions support the sustainability ambitions of both semiconductor manufacturers and Pfeiffer Vacuum+Fab Solutions, while also contributing to operational performance.

Interactive digital displays bring semiconductor manufacturing to life
A highlight of the booth will be an interactive semiconductor fab touch screen, offering a virtual tour through a modern semiconductor manufacturing facility. The digital experience demonstrates where Pfeiffer technologies are deployed throughout the production process, from cleanroom environments and wafer handling areas to sub-fab infrastructure and emissions treatment. This provides visitors with a comprehensive view of the company's portfolio and its role in enabling efficient and reliable semiconductor manufacturing, backed by end-to-end sub-fab services tailored to customer requirements.

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